Amendments to the Claims

1-45. (Cancelled)

46. (Previously presented) A method for fabricating a transparent conductive film for use in a transparent touch panel in which a lower electrode and an upper electrode are stacked so as to be spaced from each other by spacers, the transparent conductive film being provided on an electrode substrate of at least one of the electrodes and thereby forming the electrode, the method comprising:

forming an indium oxide - tin oxide film so that the film has, in its surface shape, an arithmetic mean roughness (Ra) within a range of 0.4 nm $\leq$ Ra $\leq$ 3.0 nm and a root-mean-square roughness (Rms) within a range of 0.6 nm $\leq$ Rms $\leq$ 2.0 nm, by a coating or printing process using a sol-gel material, where at least an organometallic compound constituting the sol-gel material is composed of indium and tin and has a constituent weight ratio of indium to tin that 5 wt% $\leq$ {Sn/(In+Sn)}$\times$100 $\leq$ 15 wt%.

47. (Cancelled)

48. (Previously presented) A method for fabricating a transparent conductive film for use in a transparent touch panel in which a lower electrode and an upper electrode are stacked so as to be spaced from each other by spacers, the transparent conductive film being provided on an electrode substrate of at least one of the electrodes and thereby forming the electrode, the method comprising:

after coating or printing with a sol-gel material by a coating or printing process using the sol-gel material, performing an initially drying process; then performing an oxidation burning process at a temperature increasing rate of 40°C - 60°C per minute within a temperature range of 200°C - 400°C; and subsequently performing a reduction burning process, thereby forming an indium oxide - tin oxide film so that the film has, in its surface shape, an arithmetic mean roughness (Ra) within a range of 0.4 nm $\leq$ Ra $\leq$ 3.0 nm and a root-mean-square roughness (Rms) within a range of 0.6 nm $\leq$ Rms $\leq$ 2.0 nm.

49. (Cancelled)

50. (Previously presented) A method for fabricating a transparent conductive film for use in a transparent touch panel according to Claim 46, wherein when the transparent conductive film is formed by the coating or printing process using the sol-gel material, the method comprising:

after coating or printing with the sol-gel material, performing an initially drying process; then performing an oxidation burning process at a temperature increasing rate of 40°C - 60°C per minute within a temperature range of 200°C - 400°C; and subsequently performing a reduction burning process, thereby forming the transparent conductive film.

51. (Cancelled)

52. (Previously presented) A transparent conductive film for use in a transparent touch panel fabricated by the method for fabricating a transparent conductive film for use in a transparent touch panel according to Claim 46.

53. (Cancelled)

54. (Previously presented) A transparent conductive film for use in a transparent touch panel fabricated by the method for fabricating a transparent conductive film for use in a transparent touch panel according to Claim 48.

55. (Cancelled)